

**Notice of References Cited**

Application/Control No.

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Applicant(s)/Patent Under  
Reexamination  
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Examiner

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Art Unit

2813

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-4,985,373	01-1991	Levinstein et al.	438/620
	C	US-			
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	K	US-			
	L	US-			
	M	US-			

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**NON-PATENT DOCUMENTS**

Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)

*	U	Smolinsky et al, "Reactive Ion Etching of Silicon oxides with Ammonia and Trifluoromethane, the Role of Nitrogen in the Discharge", J. Electrochem. Soc.: Solid-State Science and Technology, Vol 129 No. 5, May 1982, pp1036-1039.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.